



Docket No.: 246309US40



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COMMISSIONER FOR PATENTS  
ALEXANDRIA, VIRGINIA 22313

RE: Application Serial No.: 10/729,983

Applicants: Hiroyuki NAGASAWA

Filing Date: December 9, 2003

Allowed Date: August 10, 2006

For: SEMICONDUCTOR AND SEMICONDUCTOR  
SUBSTRATE, METHOD OF MANUFACTURING  
THE SAME, AND SEMICONDUCTOR DEVICE

Group Art Unit: 2826

Examiner: ANDUJAR, L

SIR:

Attached hereto for filing are the following papers:

**Comments on Statement of Reasons for Allowance**

Our credit card payment form in the amount of \$0.00 is attached covering any required fees. In the event any variance exists between the amount enclosed and the Patent Office charges for filing the above-noted documents, including any fees required under 37 C.F.R. 1.136 for any necessary Extension of Time to make the filing of the attached documents timely, please charge or credit the difference to our Deposit Account No. 15-0030. Further, if these papers are not considered timely filed, then a petition is hereby made under 37 C.F.R. 1.136 for the necessary extension of time. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

OBLON, SPIVAK, McCLELLAND,  
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DOCKET NO: 246309US40



**IN THE UNITED STATES PATENT & TRADEMARK OFFICE**

IN RE APPLICATION OF : ALLOWED: AUGUST 10, 2006  
HIROYUKI NAGASAWA : EXAMINER: ANDUJAR, L  
SERIAL NO: 10/729,983 :  
FILED: DECEMBER 9, 2003 : GROUP ART UNIT: 2826  
FOR: SEMICONDUCTOR AND :  
SEMICONDUCTOR SUBSTRATE,  
METHOD OF MANUFACTURING THE  
SAME, AND SEMICONDUCTOR DEVICE

**COMMENTS ON STATEMENT OF REASONS FOR ALLOWANCE**

COMMISSIONER FOR PATENTS  
ALEXANDRIA, VIRGINIA 22313

SIR:

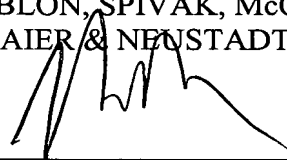
In response to the Notice of Allowability dated August 10, 2006, Applicant respectfully submits comments on the statement of reasons for allowance regarding the above-identified application.

The statement of reasons for allowance provided at page 2, item 3 of the Notice of Allowability indicates that "the prior art shows some aspect of the instant invention but does not suggest ... a transition region ... having a thickness of 5 micrometers or less and a gradient defect density of  $4 \times 10^9/\text{cm}^3$  (claims 7, 14 and 27)."

However, it is respectfully submitted that Claims 7, 14 and 27 recite that “a transition region ... having a thickness of 5  $\mu\text{m}$  or less and *a gradient of defect density of  $4 \times 10^9/\text{cm}^3$  or more*” (emphasis added in italic).

Respectfully submitted,

OBLON, SPIVAK, McCLELLAND,  
MAIER & NEUSTADT, P.C.



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(OSMMN 06/04)

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